

DISCLOSURE OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT

**GROUP
2834**

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER

ART (Including Author, Title, Date, Pertinent Pages, Etc.)

| | | |
|----|---|---|
| Lt | E | M. E. Williams et al., <i>Magnetic Levitation Scanning Stages for Extreme Ultraviolet Lithography</i> , ASPE 14 th annual meeting, Monterey CA., November 1999 |
| Lt | F | John B. Wronosky, et al., <i>Wafer and Reticle Positioning System for the Extreme Ultraviolet Lithography Engineering Test Stand</i> , SPIE, February 2000 |
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EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.